

SPIE Optics & Photonics, 14 August 2019

Polarization Effects Modeling with Field Tracing

Site Zhang¹, Christian Hellmann², and Frank Wyrowski³

¹ LightTrans International UG

² Wyrowski Photonics GmbH

³ Applied Computational Optics Group, Friedrich-Schiller-Universität Jena



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Jena, Germany



LightTrans International



University of Jena



Wyrowski Photonics



Optical Design Software and Services



Motivation



• Laser cavity with crystal for vector beam generation

Motivation



Motivation



Scope of This Work



Field Tracing Concept

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F. Wyrowski and M. Kuhn, "Introduction to field tracing," Journal of Modern Optics 58, 449-466 (2011)

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M. Kuhn, F. Wyrowski, and C. Hellmann, "Non-sequential optical field tracing," in Advanced Finite Element Methods and Applications, by T. Apel and O. Steinbach. Vol. 66, 257–273 (2013)



F. Wyrowski, "Unification of the geometric and diffractive theories of electromagnetic fields," Proc. DGaO (2017).

Single Solver for Complete System?



Finite element method (FEM) analysis of a silver nano-disc www. jcmwave.com



Plasmonic waveguide filters with nanodisk resonators, FDTD simulation www.optiwave.com

Single Solver for Complete System?



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Field Tracing – Connecting Field Solvers



by fulfilling boundary conditions

Field Tracing Operators



Characterization of Optical Anisotropy

- Constitutive relation
 - Relating the ${m E}/{m H}$ -fields and ${m D}/{m B}$ -fields



with the permittivity tensor $\underline{\epsilon}$, permeability tensor μ

– We neglect optical-rotation tensor $\underline{\rho}$ here; but there is not limitation to include it



Maxwell's Equations for Anisotropic Media

• Field equations in matrix form

$$\frac{\mathrm{d}}{\mathrm{d}z} \begin{pmatrix} \tilde{E}_x(\boldsymbol{\kappa}, z) \\ \tilde{E}_y(\boldsymbol{\kappa}, z) \\ \tilde{H}_x(\boldsymbol{\kappa}, z) \\ \tilde{H}_y(\boldsymbol{\kappa}, z) \end{pmatrix} = \mathrm{i}k_0 \begin{pmatrix} \tilde{\Omega}_{11}(\boldsymbol{\kappa}) & \tilde{\Omega}_{12}(\boldsymbol{\kappa}) & \tilde{\Omega}_{13}(\boldsymbol{\kappa}) & \tilde{\Omega}_{14}(\boldsymbol{\kappa}) \\ \tilde{\Omega}_{21}(\boldsymbol{\kappa}) & \tilde{\Omega}_{22}(\boldsymbol{\kappa}) & \tilde{\Omega}_{23}(\boldsymbol{\kappa}) & \tilde{\Omega}_{24}(\boldsymbol{\kappa}) \\ \tilde{\Omega}_{31}(\boldsymbol{\kappa}) & \tilde{\Omega}_{32}(\boldsymbol{\kappa}) & \tilde{\Omega}_{33}(\boldsymbol{\kappa}) & \tilde{\Omega}_{34}(\boldsymbol{\kappa}) \\ \tilde{\Omega}_{41}(\boldsymbol{\kappa}) & \tilde{\Omega}_{42}(\boldsymbol{\kappa}) & \tilde{\Omega}_{43}(\boldsymbol{\kappa}) & \tilde{\Omega}_{44}(\boldsymbol{\kappa}) \end{pmatrix} \begin{pmatrix} \tilde{E}_x(\boldsymbol{\kappa}, z) \\ \tilde{E}_y(\boldsymbol{\kappa}, z) \\ \tilde{H}_x(\boldsymbol{\kappa}, z) \\ \tilde{H}_x(\boldsymbol{\kappa}, z) \\ \tilde{H}_y(\boldsymbol{\kappa}, z) \end{pmatrix}$$
An ordinary differential equation below
$$\frac{\mathrm{d}}{\mathrm{d}z} f(z) = af(z)$$
has solution in the general form of
$$f(z) = C \exp(\gamma z) \bullet$$

Maxwell's Equations for Anisotropic Media

• Field equations in matrix form

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Maxwell's Equations for Anisotropic Media

· Field equations in matrix form







Experimental measurement from reference









 $(oldsymbol{\kappa},\omega)$



Extended Applications $\begin{pmatrix} \epsilon & 0 & 0 \\ 0 & \epsilon & 0 \\ 0 & 0 & \epsilon \end{pmatrix} \Rightarrow \begin{pmatrix} \epsilon_{11} & \epsilon_{12} & \epsilon_{13} \\ \epsilon_{21} & \epsilon_{22} & \epsilon_{23} \\ \epsilon_{31} & \epsilon_{32} & \epsilon_{33} \end{pmatrix}$ Induced birefringence

Laser Crystal Packaging and Stress-Induced Birefringence

- Solderjet bumping technique
 - high mechanical strength and stability
 - hermetical sealing and vacuum compatibility
 - radiation resistance
 - miniaturization and sub-µm precision

P. Ribes-Pleguezuelo, S. Zhang, E. Beckert, R. Eberhardt, F. Wyrowski, and A. Tünnermann, "Method to simulate and analyse induced stresses for laser crystal packaging technologies," Opt. Express **25**, 5927-5940 (2017)



solderjet bumping technique (pictures from Frauenhofer IOF)

How does induced birefringence affect the polarization?

- Stress-induced birefringence
 - relation between stress and optical permittivity



• Input field



- Wavelength 1064 nm
- Fundamental Gaussian
- Waist diameter 100 µm

• YAG crystal

(a) No stress

• Output field



• Input field



• YAG crystal

(b) Test stress

• Output field



- Wavelength 1064 nm
- Fundamental Gaussian
- Waist diameter 100 µm

Input field • YAG crystal Output field **−**6.0 µV/m $|E_{\chi}|$ $|E_{\chi}|$ (c) Higher stress $|E_y|$ 0.9 V/m $|E_y|$ Simulation time ~4 seconds per case Wavelength 1064 nm (Intel Core i7-4910MQ @2.9GHz) **Fundamental Gaussian**

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Waist diameter 100 µm

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Idealized Model for Anisotropic Components





S. Zhang, H. Partanen, C. Hellmann, and F. Wyrowski, "Non-paraxial idealized polarizer model," Opt. Express 26, 9840-9849 (2018)



S. Zhang, H. Partanen, C. Hellmann, and F. Wyrowski, "Non-paraxial idealized polarizer model," Opt. Express 26, 9840-9849 (2018)



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VirtualLab Fusion – Connecting Field Solvers



